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Application No.: 09/832,093
Group Art Unit: 2823
Title: Film Forming Method in which Flow Rate

Fig. 1A

SMALL QUANTITY
 SiH_4 GAS (PIPE 1)

Fig. 1B

LARGE QUANTITY
 SiH_4 GAS (PIPE 4)

Fig. 1C

Ar GAS (PIPES 3, 6)

Fig. 1D

O_2 GAS (PIPES 2, 5)

Fig. 1E

HIGH FREQUENCY POWER 19

